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30. (Amended) A photosensitive resin composition according to claim 25, wherein said diamine is a diaminodiphenyl ether.

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31. (Amended) A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound and (3) a photoinitiator.

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34. (Amended) The photosensitive resin composition according to claim 31, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

REMARKS

Applicants have amended their claims in order to further clarify the definition of various aspects of the present invention. In particular, each of claims 10, 25 and 31 has been amended to recite that the composition also includes an addition-polymerizable compound and a photoinitiator. In view of these amendments of claims 10, 25 and 31, claims 20, 26, 27, 32 and 33 have been canceled without prejudice or disclaimer, and dependencies of claims 21, 28, 30 and 34 have been amended.

The rejection of claims 10-14 and 20-36 under the second paragraph of 35 USC §112, as being incomplete for omitting essential elements, set forth in Item 3 on page 2 of the Office Action mailed April 25, 2001, is noted. Applicants now recite the addition-polymerizable compound in each of the independent claims (claims 10, 25 and 31). Accordingly, this basis for rejection of the claims under the second paragraph of 35 USC §112, set forth in Item 3 on page 2 of the Office Action mailed April 25, 2001, is moot.

The rejection of all of the presently pending claims under the second paragraph of 35 USC §112, as being indefinite, the Examiner contending (see Item 4 on page 3 of the Office Action mailed April 25, 2001) that the limitation "polymerization initiator" in line 6 of claim 10 does not have sufficient antecedent basis in the specification, is noted. The independent claims in the application, claims 10, 25 and 31, have been amended to recite a "photoinitiator". As for such "photoinitiator", note page 2, lines 9-11 of Applicants' specification; see also, for example, page 12, line 26 to page 13, line 21, of Applicants' specification. Clearly, there is sufficient antecedent basis in Applicants' specification for recitation of a "photoinitiator". Accordingly, it is respectfully submitted that the basis for the rejection under the second paragraph of 35 USC §112, as set forth in Item 4 on page 2 of the Office Action mailed April 25, 2001, is moot.

The undersigned notes the rejection of claims 1-9 under 35 USC §103(a) as being unpatentable over Ohbayashi et al. '391 or Aldrich et al., set forth in Item 6 on pages 3-5 of the Office Action mailed April 25, 2001. Note that claims 1-9 have been previously canceled, from the above-identified application. Accordingly, basis for this rejection of claims 1-9 on prior art grounds, as set forth in Item 6 on pages 3-5 of the Office Action mailed April 25, 2001, is not understood.

In any event, attention is respectfully directed to the first paragraph on page 5 of this Office Action mailed April 25, 2001. Herein, the Examiner contends that the evidence includes the presence of an addition-polymerizable compound "which is not recited by claim 10"; and thus, the claims are not seen as being commensurate in scope with the declaration evidence to overcome the rejections under 35 USC §103(a). As appreciated from the foregoing, Applicants have amended the claims, including claim 10, to recite that the composition includes an addition-polymerizable compound. Even were the prior art rejection to be applied against the claims in the application considered by the Examiner in the Office Action mailed April 25, 2001, it is respectfully submitted that all of the composition claims presently in the application include the addition-polymerizable compound; and that any possible *prima facie* case of

obviousness established by the teachings of the applied references is overcome by the evidence of unexpected results presently of record.

In view of the foregoing comments and amendments to the claims, reconsideration and allowance of all claims remaining in the application are respectfully requested.

Attached hereto is a marked-up version of the changes made to the specification and claims by the current amendment. The attached page is captioned "**VERSION WITH MARKINGS TO SHOW CHANGES MADE**".

To the extent necessary, applicants petition for an extension of time under 37 CFR §1.136. Please charge any shortage in the fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account No. 01-2135 (511.33114VV5) and please credit any excess fees to such deposit account.

Respectfully submitted,

ANTONELLI, TERRY, STOUT & KRAUS, LLP

A handwritten signature in black ink, appearing to read "William I. Solomon", with a long horizontal flourish extending to the right.

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ATTACHMENT A

VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the Claims:

Claims 10, 21, 25, 28, 30, 31 and 34 have been amended as indicated below:

10. (Twice Amended) A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof as a reactant, a 20 μm film thickness of said polyimide precursor having a transmittance, at 365 nm, of at least 40%; [and] (2) an addition-polymerizable compound; and (3) a [polymerization initiator] photoinitiator.

21. (Amended) A photosensitive resin composition according to claim [20] 10, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

25. (Amended) A photosensitive resin composition which comprises (1) a polyimide precursor formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound, and (3) a

photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light.

28. (Amended) A photosensitive resin composition according to claim [27] 25, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

30. (Amended) A photosensitive resin composition according to claim [27] 25, wherein said diamine is a diaminodiphenyl ether.

31. (Amended) A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound and (3) a photoinitiator.

34. (Amended) The photosensitive resin composition according to claim [33] 31, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.